PATENT ASSIGNMENT

Electronic Version v1.1 Stylesheet Version v1.1

SUBMISSION TYPE: NEW ASSIGNMENT

NATURE OF CONVEYANCE: LICENSE

CONVEYING PARTY DATA

Name	Execution Date
IMS Nanofabrication AG	03/03/2010

RECEIVING PARTY DATA

Name:	Intel Corporation
Street Address:	2200 Mission College Blvd.
City:	Santa Clara
State/Country:	CALIFORNIA
Postal Code:	95052

PROPERTY NUMBERS Total: 23

Property Type	Number
Patent Number:	5801388
Patent Number:	5742062
Patent Number:	5874739
Patent Number:	6326632
Patent Number:	6661015
Patent Number:	6858118
Patent Number:	6768125
Patent Number:	6909103
Application Number:	10951087
Patent Number:	7084411
Patent Number:	7214951
Patent Number:	7388217
Patent Number:	7436120
Application Number:	11719320
Patent Number:	7276714
	PATENT

REEL: 024055 FRAME: 0092

Application Number:	11816353
Application Number:	11816059
Application Number:	12294262
Application Number:	11951543
Application Number:	11978661
Application Number:	12051087
Application Number:	12120130
Application Number:	12178153

CORRESPONDENCE DATA

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ATTORNEY DOCKET NUMBER:	AMK-5452-5
NAME OF SUBMITTER:	Alan M. Kagen

Total Attachments: 7

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IMS NANOFABRICATION AG CONFIRMATION to the United States Patent and Trademark Office

IMS Nanofabrication AG, a Vienna, Austria corporation, having a place of business at Schreygasse 3 and its wholly owned subsidiaries (hereinafter "**IMS**") herewith confirms to the United States Patent and Trademark Office (hereinafter "**USPTO**") as follows:

Subject to a Development Agreement dated October 23, 2009, entered into by and between IMS and Intel Corporation, a Delaware corporation, having its principal place of business at 2200 Mission College Blvd., Santa Clara CA 95052 (hereinafter "Intel"), IMS has granted to Intel non exclusive license rights ("Licenses") to patents registered with USPTO as follows:

Patent Title	Patent No.
Particle Beam in particular ionic Optic	No: US 5,801,388
Imaging System Arrangement for Masked Beam Lithography	No: US 5,742,062
by Means of Electrically Charged Particles	No. 110 5 974 799
Arrangement for Masked Beam Lithography by Means of Electrically Charged Particles	No: US 5,874,739
Particle-Optical Imaging System for	No: US 6,326,632 B1
Lithography Purposes Pattern Lock System	No: US 6,661,015 B2
Pattern Lock System	NO. US 0,001,013 B2
Apparatus for Enhancing the Lifetime of Stencil Masks	No: US 6,858,118 B2
Maskless Particle Beam System for Exposing a Pattern on a Substrate	No: US 6,768,125 B2
lon Irradiation of a target at very high and very low kinetic ion energies	No: US 6,909,103
Particle-optic column	Publication No: US 2005-0072933
Pattern-definition device for maskless particle-beam exposure apparatus	No: US 7,084,411
Charged-Particle Multi-Beam Exposure Apparatus	No: US 7,214,951 B2
Particle-optical projection system	No: US 7,388,217
Compensation of Magnetic Fields	No: US 7,436,120
Pattern Lock System for Particle-Beam	Publication No: US 2009146082 A1
Advanced Pattern Definition for Particle- Beam Processing	No: US 7,276,714
Charged-Particle Exposure Apparatus	Publication No: US 2008-0258084 A1
Charged-Particle Exposure Apparatus with Electrostatic Zone Plate	Publication No: US 2008-0230711

Particle-Beam Exposure Apparatus with Overall-Modulation of a Patterned Beam	Publication No: US 2009-0200495 A1		
Particle-Beam Apparatus with improved Wien-type Filter	Publication No: US 2008-0149846 A1		
Charged Particle Exposure Apparatus	Publication No: US 2008-0099693 A1		
Method for Maskless Particle-Beam Exposure	Publication No: US 2008-0237460 A1		
Pattern Definition Device having Distinct Counter-Electrode Array Plate	Publication No: US 2008-0283767 A1		
Multi Beam Source	Publication No: US 2009-0026389 A1		

Further details with regard to the Licenses are included in the Development Agreement, excerpts of which are attached hereto in <u>Appendix ./1</u>

IMS NANOFABRICATION AG

Ву: __/

Name: M. SAYENC

Title: CEO

Date: Mary 3 td, 2010

PATENT

REEL: 024055 FRAME: 0095

Appendix . 11

IMS NANOFABRICATION AG and INTEL CORPORATION **DEVELOPMENT AGREEMENT**

This Agreement (the "Agreement") is entered into as of October 23, 2009 ("Effective Date") by and between IMS Nanofabrication AG, a Vienna, Austria corporation, having a place of business at Schreygasse 3 and its majority owned subsidiaries (hereinafter "IMS"), and Intel Corporation, a Delaware corporation, having its principal place of business at 2200 Mission College Blvd., Santa Clara CA 95052 and its majority owned subsidiaries (hereinafter "Intel"). IMS and Intel are sometimes referred to as a "Party" and collectively referred to as the "Parties".

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Intel Confidential

- 13.3. IMS hereby grants to Intel license rights to the IMS Intellectual Property as follows:
 - 13.3.1 Exclusive License. Except as expressly provided otherwise in this Agreement, IMS herewith grants Intel an exclusive, worldwide, transferable, royalty-free and temporally limited (convertible) license to (i) any IMS Intellectual Property save for the Transferred IMS Intellectual Property (see Section 13.3.2) and (ii) the New IMS Intellectual Property as established pursuant to the activities undertaken hereunder and duly registered in accordance with Section 10.2.
 - 13.3.2 <u>Non-Exclusive License</u>. In addition to the Exclusive License according to Section 13.3.1, IMS herewith grants Intel a non-exclusive, worldwide, non-transferable, royalty-free, perpetual license to the Transferred IMS Intellectual Property as outlined in Exhibit B.1.
 - 13.3.3 Exclusive- and non-exclusive license rights (herafter "License Rights") are herewith granted to Intel in order to make, have made, use, sell, offer to sell, or import the MBMW and MBMW Column(s) which employ or incorporate the IMS Intellectual Property. The scope of such License Rights includes the right of Intel to make or have made MBMW or MBMW Columns for third parties, subject to the royalty to IMS as outlined in Section 3.3. The use of the License Rights by Intel is strictly limited to MBMW and MBMW Columns, and Intel shall not use the License Rights for any other applications or purposes. IMS is in no way

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IN WITNESS WHEREOF, the Parties have caused this Agreement to be executed by duly authorized officers or representatives to be effective as of the date first above written.

INTEL CORPORATION		IMS NANOFABRICATION AG		
By:	Um Shiling	By:		
	CHEIS PHILIPPI	Name:		
Title:	TRAILOR COLLABORATIONS MANAGETE	Title:		
Date:_	New 5, 2009	Date:		

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IN WITNESS WHEREOF, the Parties have caused this Agreement to be executed by duly authorized officers or representatives to be effective as of the date first above written.

IMS NANOFABRICATION AG

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Ву:	By:	120	du-
Name:	Name:	MAX	BAYERE.
Title:	Title:	CEC	>
Date:	Date:	1651	5,2009

Intel Confidential

RECORDED: 03/10/2010

INTEL CORPORATION